



International Electronics Manufacturing Initiative

Humidity Effects on Sn Whisker Formation

*ECTC NEMI workshop June 1,
2005*

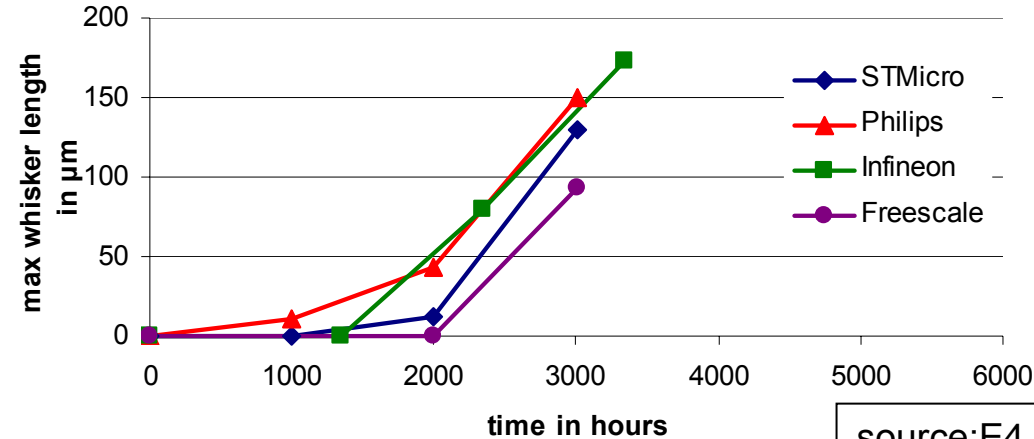
*Dr. Marc Dittes, Dr. Pascal Oberndorff, Peng Su, Paolo
Crema*

- **Overview on experimental approach**
- **Results from cross referencing**
- **Influence of relative humidity**
- **Ni-underlayer**
- **Effect of board mounting**
- **Correlation of corrosion to whisker formation**
- **Summary of findings**
- **Theoretical approach**
- **Conclusion**

- **4 companies, 5 assembly locations, 4 base materials, 4 electrolytes, 4 test locations,**
- **test conditions:**
 - **as plated**
 - **reflow simulation 215 °C / 260 °C**
 - **board assembly SnPb and SnAgCu**
 - **clean & non-clean after board assembly**
 - **60 °C / 93, 90, 85 % RH**
 - **non-condensing condition / forced condensation**
- **test package TQFP-64 – 132, 5-10 components per test leg**
- **→ more than 600 leads per datapoint**
- **Total of > 60000 leads in inspection**

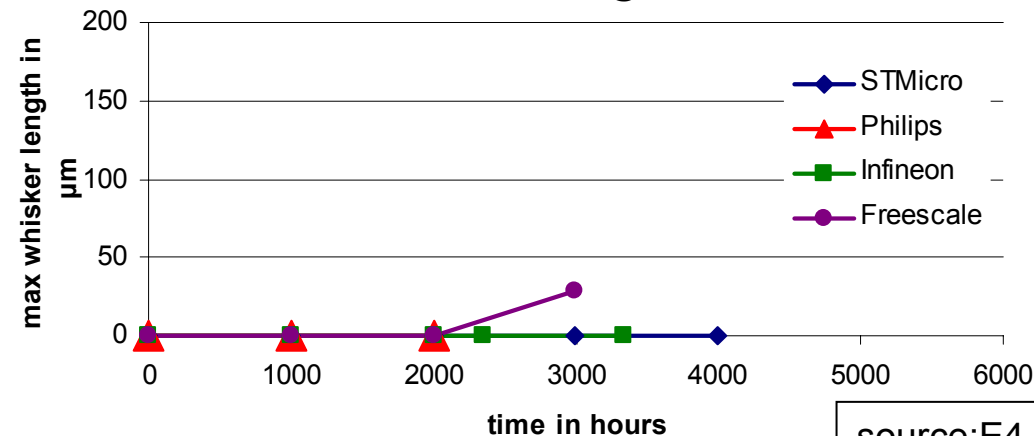
**Test condition:
60 °C / 93 % RH**

Reference sample IFX
Sn auf FeNi42

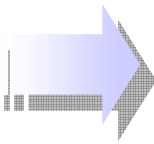


source:E4

Reference sample STM
Sn auf C7025 - reflow @ 260 °C



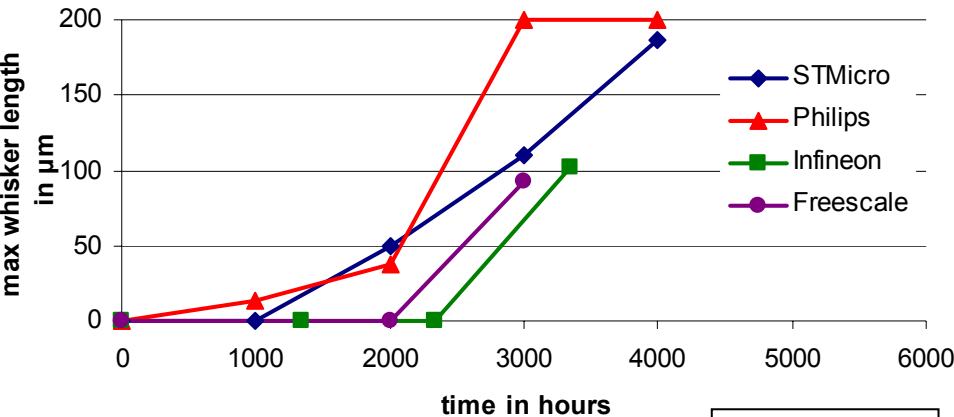
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**Very consistent
whisker growth for
both growth rate and
incubation time**

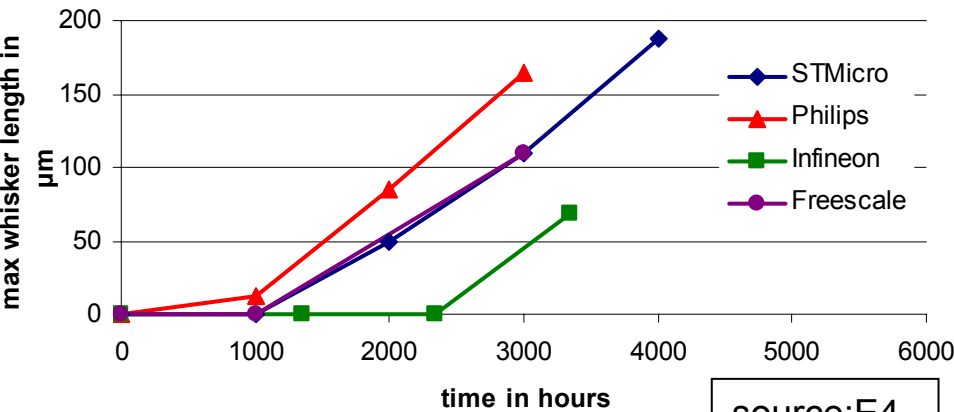
**Test condition:
60 °C / 93 % RH**

**Reference sample PHG
Sn auf C7025**

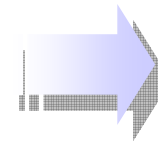


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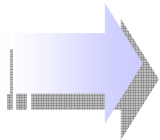
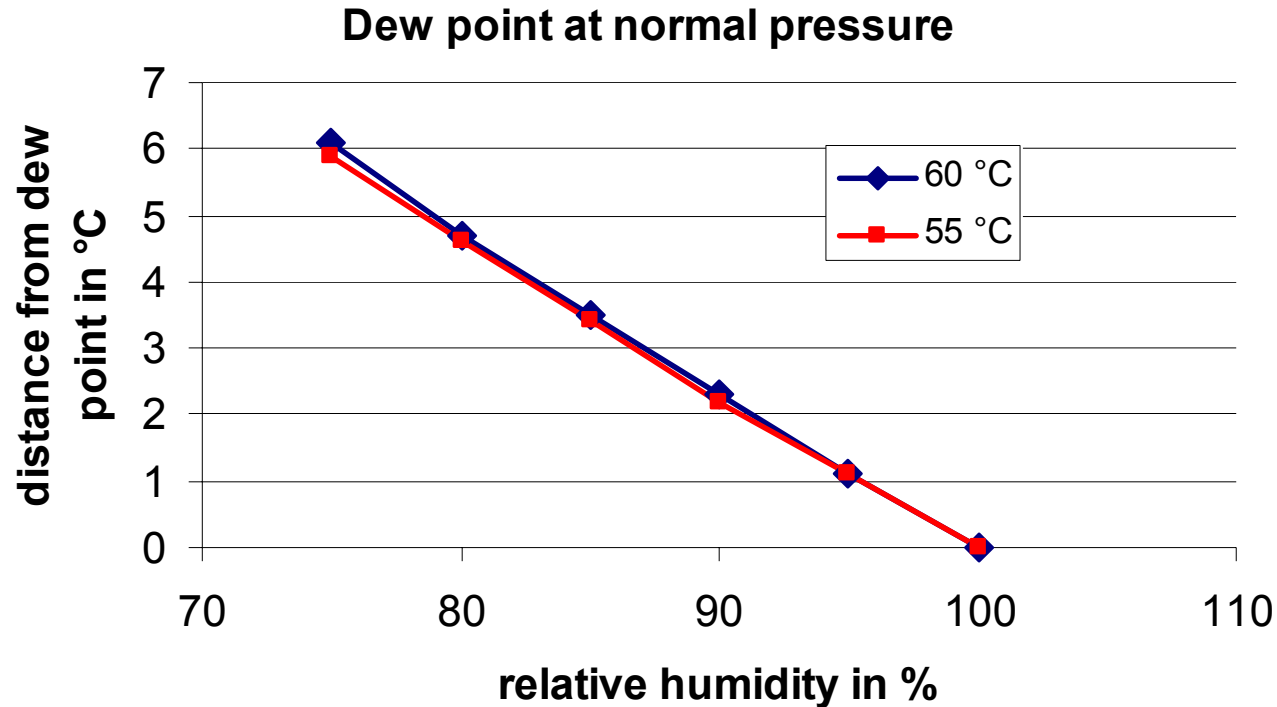
**Reference sample FSL
Sn auf C 194**



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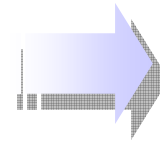
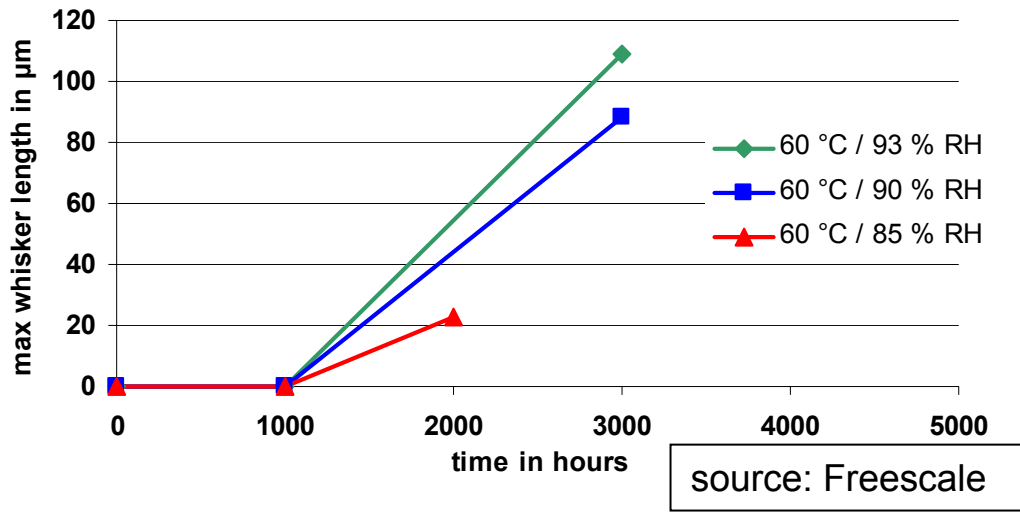


Inconsistent whisker growth for growth rate and / or incubation time



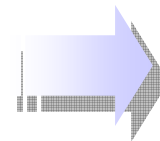
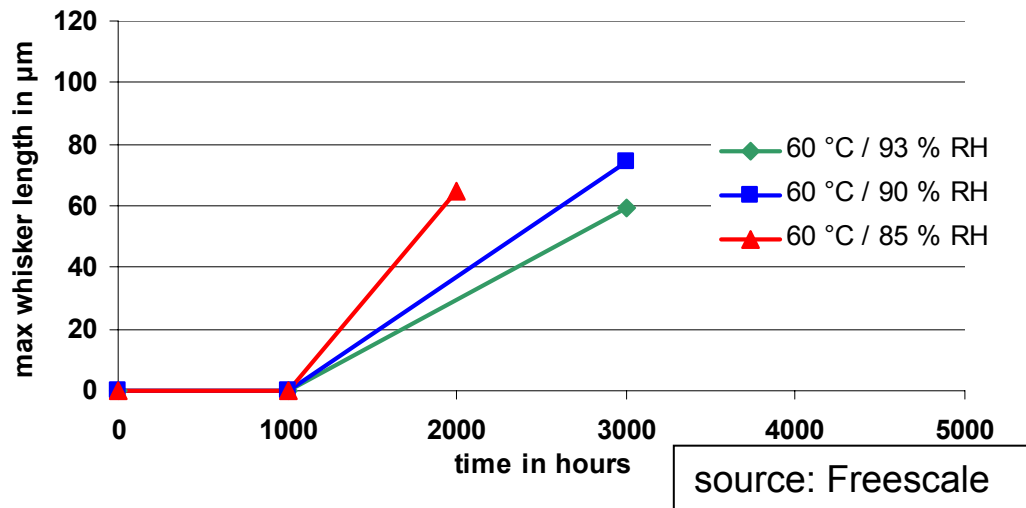
At 60 °C / 85 % RH the dew point is ~ 3,5 °C below the set temperature. In well controlled humidity chambers condensation should not happen.

Sn on Cu C7025



Apparently whisker growth dependent on humidity at constant temperature

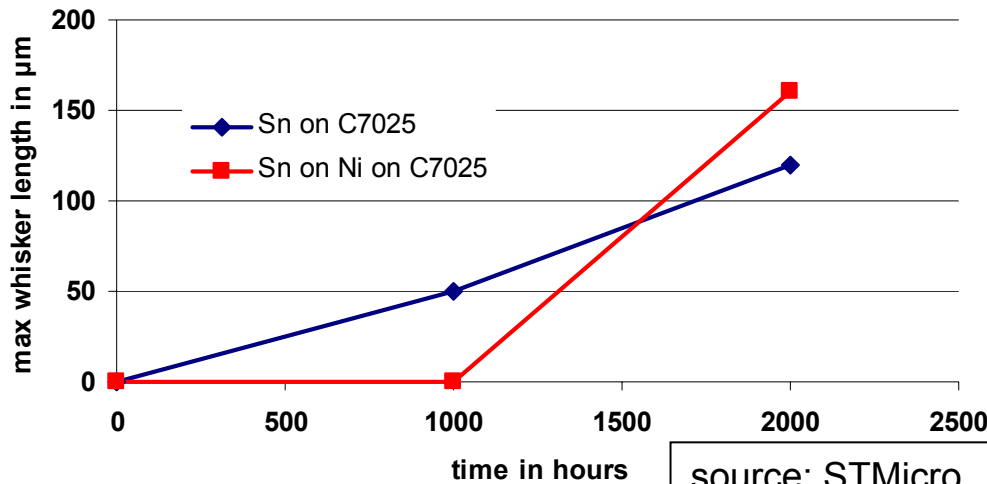
Sn on Cu C7025 reflow simulation



Whisker growth not correlated to humidity at constant temperature

Note: information on whisker density will result in consistent picture (See Peng Su's presentation)

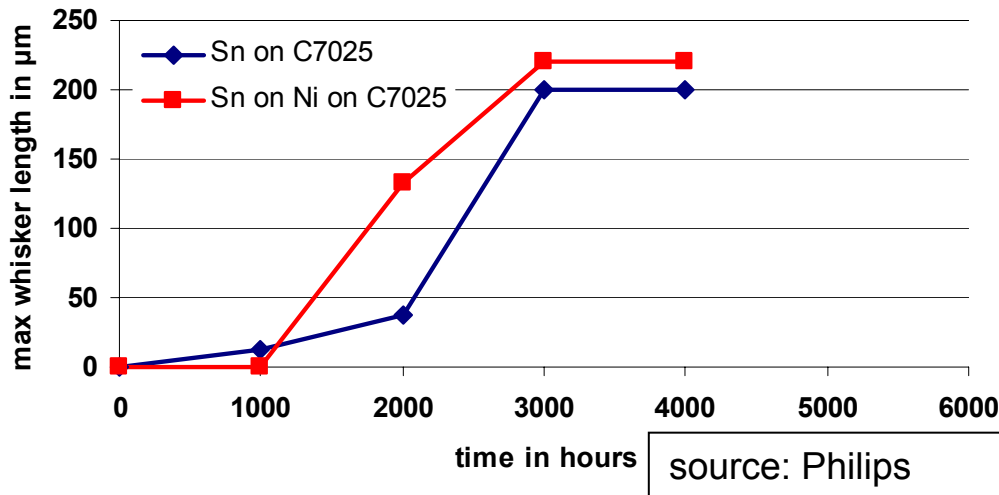
60 °C / 93 % RH
260 °C board mount simulation



1 µm Ni underlayer

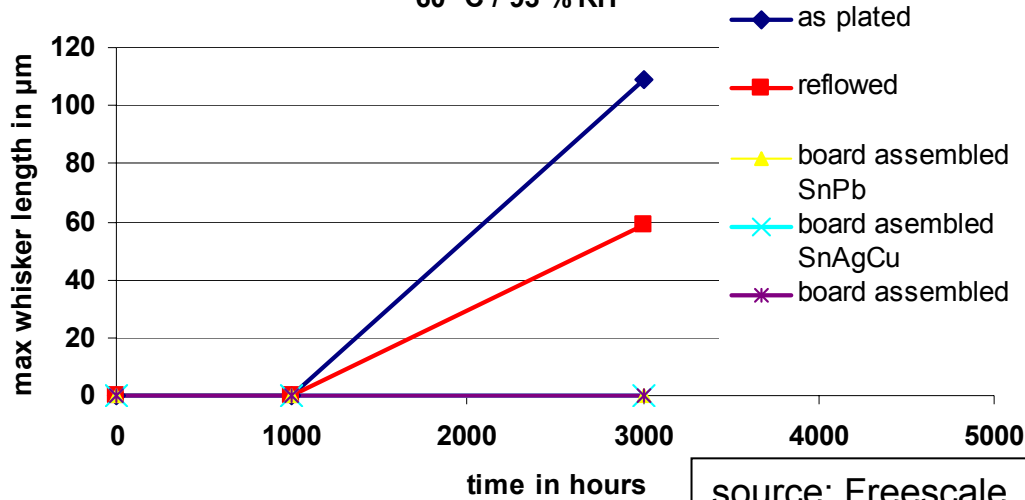
Whisker growth is comparable with and w/o Ni-underlayer in high humidity / high Temp testing

60 °C / 93 % RH



2 µm Ni underlayer

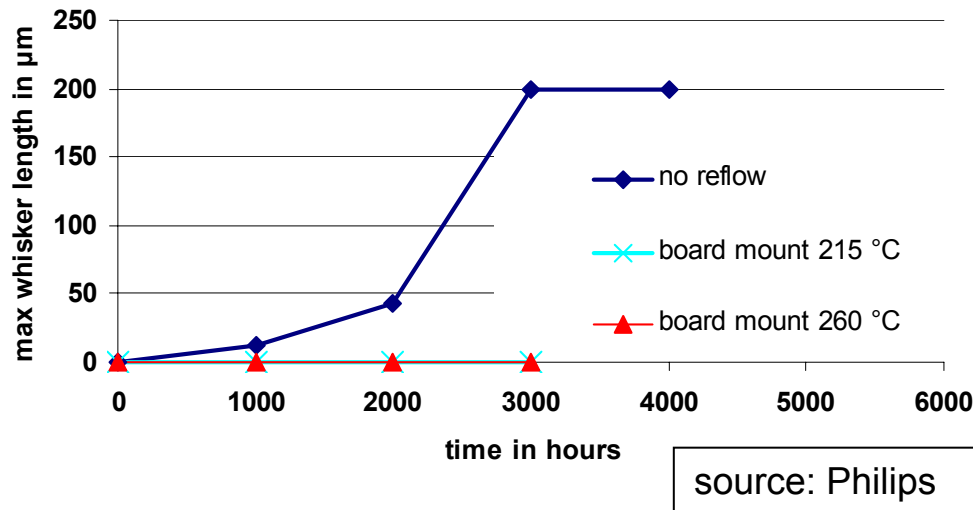
Sn on Cu C7025
60 °C / 93 % RH



LQFP132
no full wetting
of leads

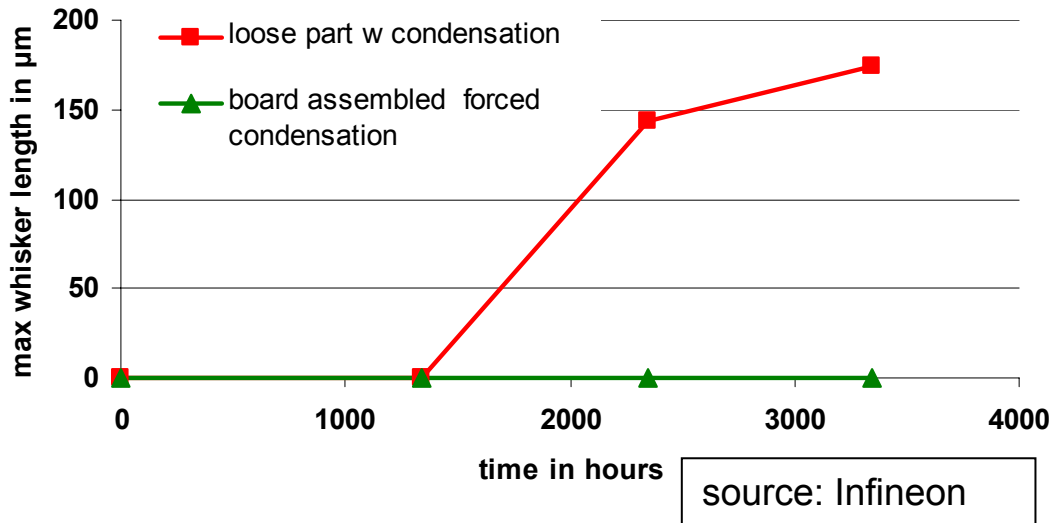
While whisker grow on loose parts, no whisker grow in board assembled state

Sn 10 µm on Cu C7025 - forced condensation



LQFP128
no full wetting
of leads

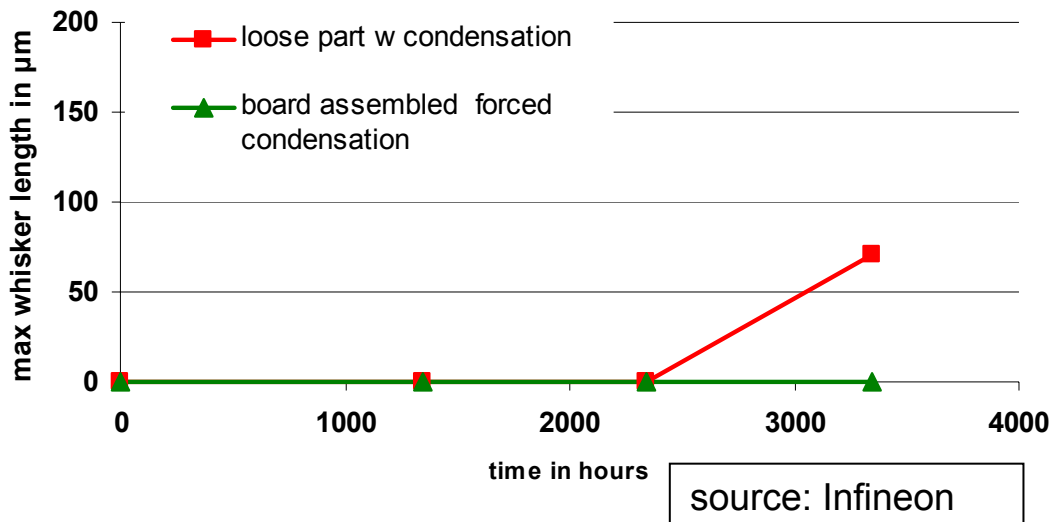
Sn 10 µm on FeNi42



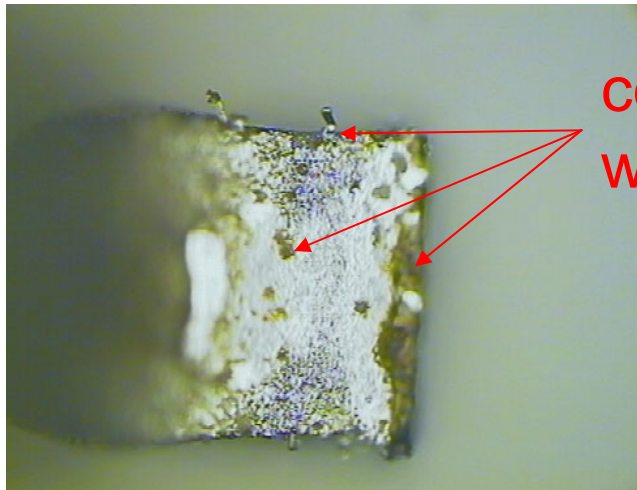
**Test condition:
60 °C / 93 % RH,
forced
condensation**

- **Significantly shorter incubation for whisker growth to start and higher growth rate for FeNi42 base material.**
- **no whisker growth in board assembled state**

Sn 10 µm on Cu Etec 64

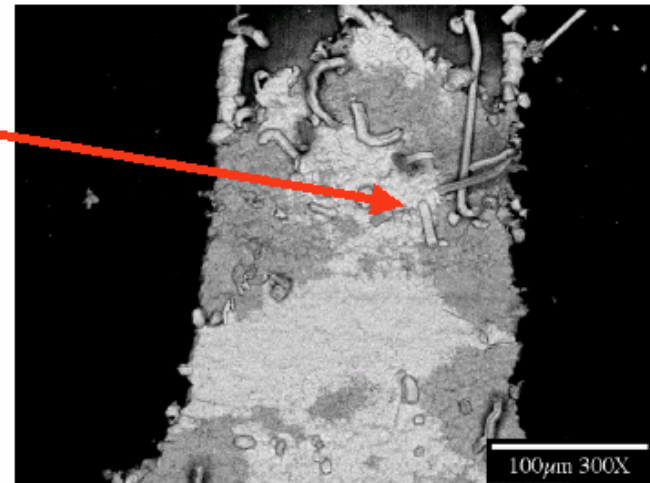


- At least 6 companies or groups (Freescale, iNEMI, Infineon, Philips, Samsung, STMicroelectronics) report on evident correlation of whiskers with visible corrosion.
- Both corrosion and whisker are preferably found close to dambar cut or lead tip (areas with exposed base material)
- Corrosion and whisker however are also found on well covered area

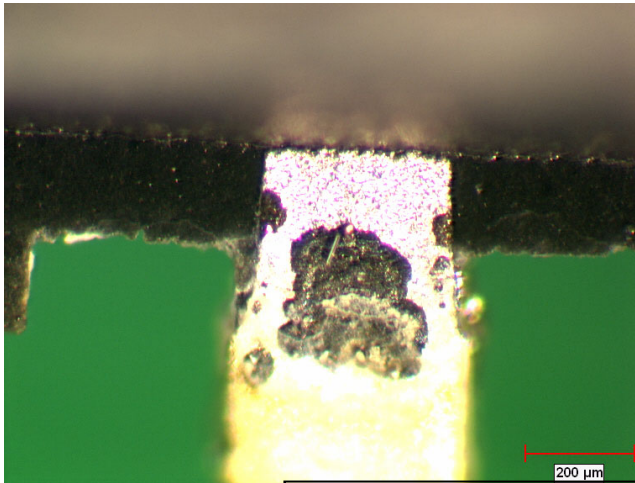


source: Infineon

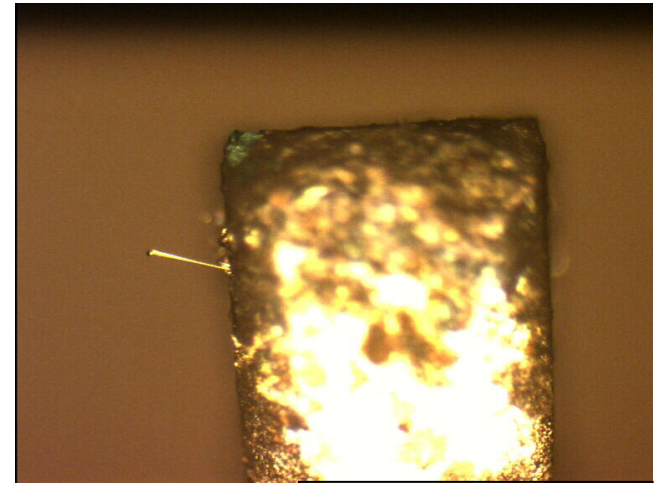
corrosion &
whisker



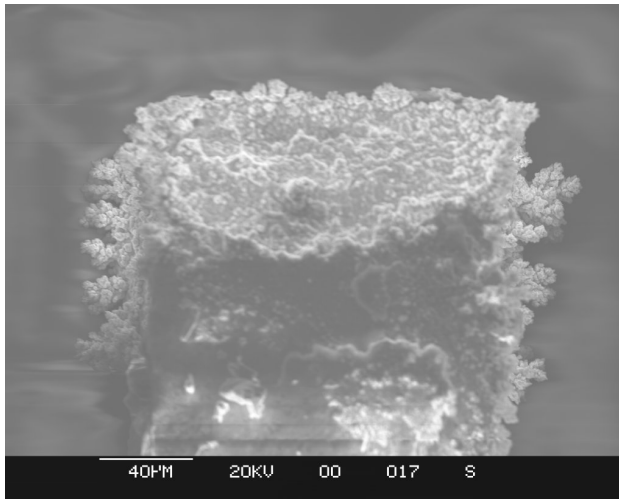
source: iNEMI



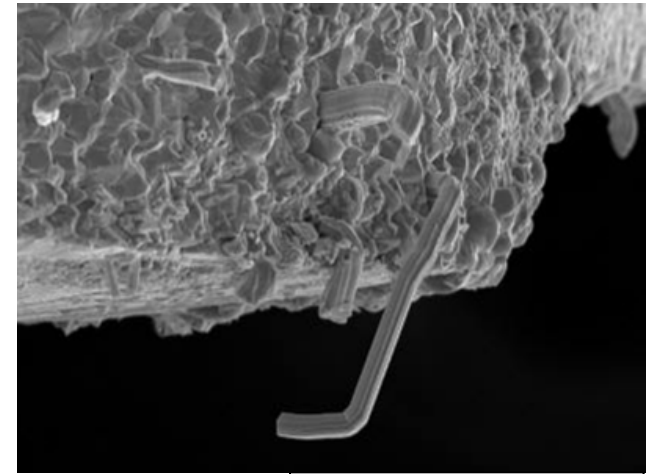
source: Philips



source: STMicro



source: STMicro



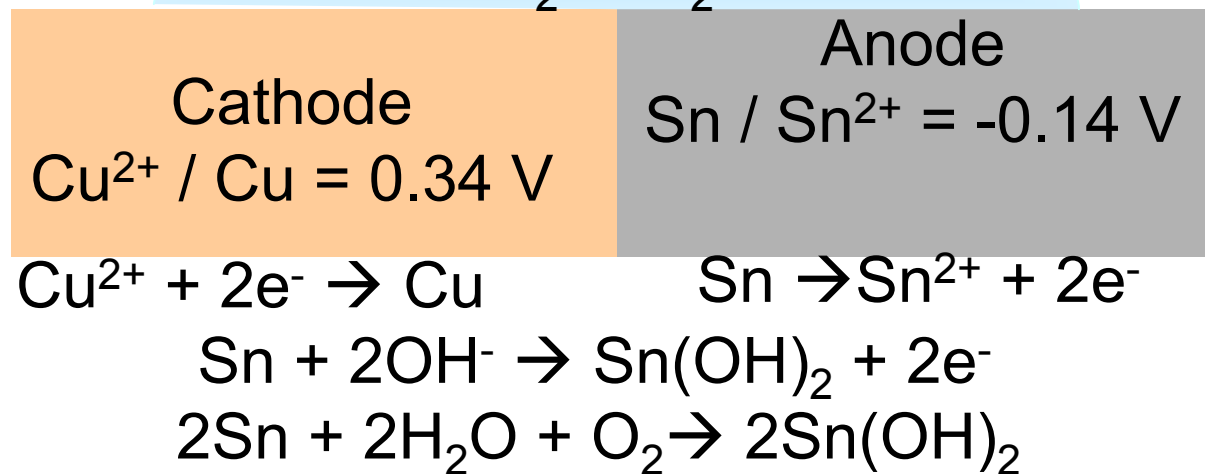
source: Freescale

- **Even by reduction of humidity to 85 % both corrosion and whisker growth observed (FSL, IFX)**
- **Condensation not necessary to result in corrosion**
- **Huge variation on same sample type in various test locations possible → control of test equipment almost impossible**
- **Most - but not restricted to - corrosion and whisker growth observed in areas close to exposed base material**
- **board assembled units do show almost no corrosion and whisker (also on non solder-wetted areas)**

- Corrosion may happen due to water condensation in association with exposed base material forming a galvanic couple (exposed base material)
- Also local defects within the tin may cause localised different nobility forming such a galvanic couple
- Monolayers of water w/o condensation may support the corrosive effect

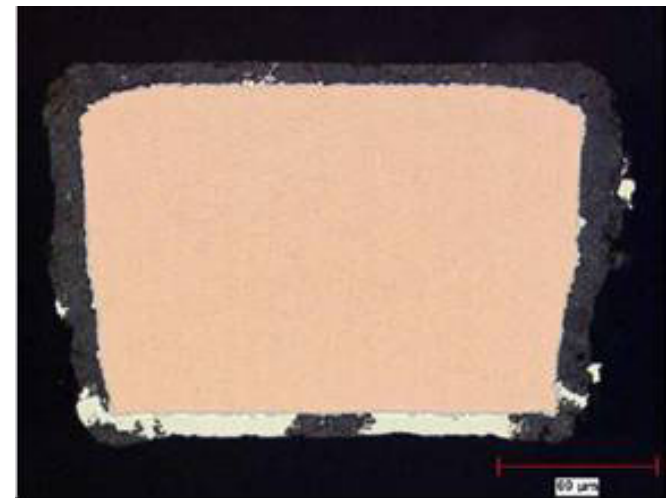
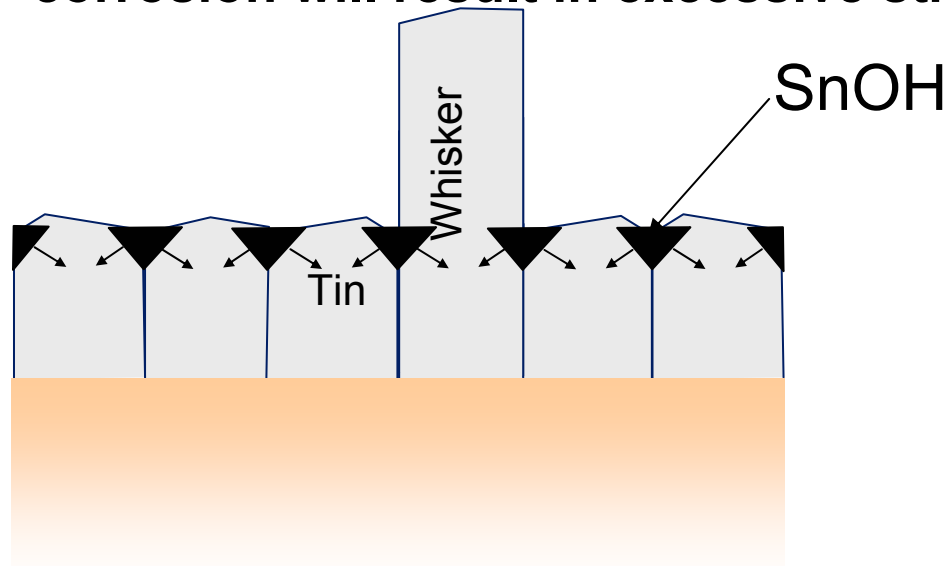


O₂ in H₂O



The formation of SnO or SnO₂ by reaction of tin with the atmosphere results in a localised volume increase by 29% or 47% (dependent on crystal structure / data source) or 32% respectively. A similar volume increase can be assumed by the formation of SnOH, or derivatives

It may be assumed that the diffusion of OH⁻ ions will be faster in the grain boundaries resulting in compressive stress within the tin layer as driving force for whisker formation. Excessive corrosion will result in excessive stress.



source: Philips

- **Besides intermetallic formation (moderate temperatures) and mismatch of cte associated with thermal cycling, high temperature/ high humidity conditions result in an additional mechanism for stress formation within a tin plating layer.**
- **This mechanism is associated to the volume increase by the corrosion of the tin**
- **Conclusively the whisker formation in high temperature / high humidity conditions is independent from diffusion barriers (regular intermetallic by post bake, Ni, Ag) at the base material / tin finish interface.**
- **However, whisker formation is strongly reduced or suppressed by soldering for board assembly.**
- **The high temperature / high humidity test is a corrosion test rather than a whisker test and shall be applied to components in their field use conditions only**